

ABSTRACT

A chemical amplification resist composition comprising a treated resin (1) obtained by contacting crude resin (1) with activated carbon, an acid generator and a 5 solvent,
wherein resin (1) is
(a) a (meth)acrylic resin which is insoluble or poorly soluble in an alkali aqueous solution and becomes soluble in an alkali aqueous solution by the action of an acid, and which comprises a repeating unit having an alicyclic hydrocarbon group in its side 10 chain or
(b) a styrenic resin which is insoluble or poorly soluble in an alkali aqueous solution and becomes soluble in an alkali aqueous solution by the action of an acid, and which comprises a repeating unit derived from hydroxystyrene, and a process for producing the same.